

Amendments to the Claims

1. **(Currently Amended)** A substrate cleaning apparatus comprising:

~~a plurality of substrate rotating rollers for gripping the periphery of a substrate and rotating the substrate;~~

a cleaning roller ~~capable of rotating~~ adapted to rotate and having a cleaning member ~~which is adapted to be brought into contact with at least one of an end face and/or and a bevel face of the~~ a substrate so as to perform scrub-cleaning to the at least one of the end face and/or and the bevel face; and

a power transmission mechanism for transmitting a rotating force for rotating the substrate ~~of at least one roller of the substrate rotating rollers~~ to the cleaning roller so as to rotate the cleaning roller,

wherein the power transmission mechanism has a revolution transfer ratio set such that a relative difference in velocity exists between a peripheral velocity of revolution of the cleaning member and a peripheral velocity of revolution of the substrate.

2. **(Currently Amended)** A substrate cleaning apparatus of claim 1, ~~wherein further comprising a plurality of substrate rotating rollers for gripping the periphery of the substrate and rotating the substrate~~ the power transmission mechanism has its revolution transfer ratio set such that there would be a relative difference in velocity between a peripheral velocity of revolution of the cleaning member and a peripheral velocity of revolution of the substrate.

3. **(Currently Amended)** A substrate cleaning apparatus of claim 1, further comprising a cleaning nozzle for injecting a cleaning liquid against a surface of the cleaning member to be brought into contact with the substrate.

4. **(Currently Amended)** A substrate cleaning apparatus of claim 1, further comprising a force adjusting mechanism for adjusting an amount of pushing of the cleaning member against the at least one of the end face and/or and the bevel face of the substrate.

5. **(Currently Amended)** A substrate cleaning apparatus of claim 1, ~~wherein further comprising a swingable swing arm rotatably supporting the cleaning roller is rotatably supported on the~~ a free end of a swingable swing arm thereof, wherein the swingable swing arm is biased in ~~the~~ a direction of bringing the cleaning member into contact with ~~the at least one of the end face and/or~~ and the bevel face of the substrate.

6. **(Currently Amended)** A substrate cleaning apparatus of claim 1, further ~~comprises~~ comprising a contact location adjusting mechanism for vertically adjusting a contact location of the cleaning member with the substrate in ~~the~~ a height direction of the cleaning member.

7. **(Original)** A substrate cleaning apparatus of claim 2, further comprising a cleaning nozzle for injecting a cleaning liquid against a surface of the cleaning member to be brought into contact with the substrate.

8. **(Currently Amended)** A substrate cleaning apparatus of claim 2, further comprising a force adjusting mechanism for adjusting an amount of pushing of the cleaning member against ~~the at least one of the end face and/or~~ and the bevel face of the substrate.

9. **(Currently Amended)** A substrate cleaning apparatus of claim 2, ~~wherein further comprising a swingable swing arm rotatably supporting the cleaning roller is rotatably supported on the~~ a free end of a swingable swing arm thereof, wherein the swingable swing arm is biased in ~~the~~ a direction of bringing the cleaning member into contact with ~~the at least one of the end face and/or~~ and the bevel face of the substrate.

10. **(Currently Amended)** A substrate cleaning apparatus of claim 2, further comprising a contact location adjusting mechanism for vertically adjusting a contact location of the cleaning member with the substrate in ~~the~~ a height direction of the cleaning member.

11. **(Currently Amended)** A substrate cleaning apparatus of claim 3, further comprising a force adjusting mechanism for adjusting an amount of pushing of the cleaning member against the at least one of the end face and/or the bevel face of the substrate.

12. **(Currently Amended)** A substrate cleaning apparatus of claim 3, ~~wherein further comprising a swingable swing arm rotatably supporting the cleaning roller is rotatably supported on the~~ a free end of a swingable swing arm thereof, wherein the swingable swing arm is biased in ~~the~~ a direction of bringing the cleaning member into contact with the at least one of the end face and/or the bevel face of the substrate.

13. **(Currently Amended)** A substrate cleaning apparatus of claim 3, further comprising a contact location adjusting mechanism for vertically adjusting a contact location of the cleaning member with the substrate in ~~the~~ a height direction of the cleaning member.

14. **(Currently Amended)** A substrate cleaning apparatus of claim 4, ~~wherein further comprising a swingable swing arm rotatably supporting the cleaning roller is rotatably supported on the~~ a free end of a swingable swing arm thereof, wherein the swingable swing arm is biased in ~~the~~ a direction of bringing the cleaning member into contact with the at least one of the end face and/or the bevel face of the substrate.

15. **(Currently Amended)** A substrate cleaning apparatus of claim 4, further comprising a contact location adjusting mechanism for vertically adjusting a contact location of the cleaning member with the substrate in ~~the~~ a height direction of the cleaning member.

16. **(Currently Amended)** A substrate cleaning apparatus of claim 5, further comprising a contact location adjusting mechanism for vertically adjusting a contact location of the cleaning member with the substrate in ~~the~~ a height direction of the cleaning member.

17. **(Currently Amended)** A substrate cleaning apparatus comprising:

- a pair of bases movable to come close to or to go away from each other;
- a plurality of rollers supported on the bases, the rollers ~~gripping~~ adapted to grip a periphery of a substrate;
- a substrate rotating mechanism operable to rotate the rollers ~~thereby~~ to thereby rotate the substrate; ~~and~~
- a scrub-cleaning member supported on the bases, the scrub-cleaning member adapted to cleaning clean an end face of the substrate; and
- a cleaning nozzle for directing a cleaning liquid between the scrub-cleaning member and the periphery of the substrate.

18. **(Currently Amended)** A substrate cleaning apparatus of claim 17, wherein the scrub-cleaning member comprises a cleaning roller which contacts the end face of the substrate.

19. **(Currently Amended)** A substrate cleaning apparatus of claim 18, wherein the substrate rotating mechanism transmits a rotating force ~~of~~ to the cleaning roller ~~is transmitted from the substrate rotating mechanism.~~

20. **(Original)** A substrate cleaning apparatus of claim 17, further comprising a ultrasonic nozzle directing cleaning liquid to the end face of the substrate.

21. **(Currently Amended)** A substrate cleaning apparatus of claim 17, wherein each of the rollers ~~having~~ has a groove into which the periphery of the substrate is to be inserted.